

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/625,243	07/22/2003	Andrew Perry	LAM2P426	9295
25920 MARTINE PE	7590 01/25/200 NILLA & GENCAREI	EXAMINER		
710 LAKEWAY DRIVE SUITE 200 SUNNYVALE, CA 94085			KACKAR, RAM N	
			ART UNIT	PAPER NUMBER
			1763	
SHORTENED STATUTOR	RY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE	
. 3 MO	NTHS	01/25/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

	Application No.	Applicant(s)				
Office Action Commons	10/625,243	PERRY, ANDREW				
Office Action Summary	Examiner	Art Unit				
T. 1441 NO 8475 144	Ram N. Kackar	1763	_			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory period varieties to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).				
Status	•					
1) Responsive to communication(s) filed on 15 No	<u>.</u> <u>ovember 2006</u> .					
<u> </u>	_					
3) Since this application is in condition for allowar	nce except for formal matters, pro	secution as to the merits is				
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.				
Disposition of Claims						
4) ☐ Claim(s) 8,19 and 21-23 is/are pending in the a 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 8,19 and 21-23 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	vn from consideration.					
Application Papers	•					
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) access applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Examine	epted or b) objected to by the I drawing(s) be held in abeyance. Sec ion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list of	s have been received. s have been received in Applicati ity documents have been receive (PCT Rule 17.2(a)).	on No ed in this National Stage				
Attachment(s)						
1) X Notice of References Cited (PTO-892)	4) Interview Summary	(PTO-413)				
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	nte				

Application/Control Number: 10/625,243

Art Unit: 1763

DETAILED ACTION

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 11/15/2006 has been entered.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 8, 19 and 22 are rejected under 35 U.S.C. 102(e) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Coronel et al (US 5658418).

Coronel et al disclose a plasma etching apparatus capable of determining end point (Abstract) comprising a broad spectrum light source (29 and Col 8 lines 7-16), a spectrometer (33), a lens system (31), light source optical fiber bundle (30), detector optical fiber bundle (32) while light fiber bundle and detector fiber bundle are made in a single bundle with fibers assembled together randomly (Col 8 lines 28-36), detector with discrete detection regions (regions corresponding to optical fibers contained in cables 32a and 32b) for detecting reflected

Application/Control Number: 10/625,243 Page 3

Art Unit: 1763

light from an illuminated portion of a substrate (Abstract) and selects the best signal/wavelength (specific optical signal across a frequency band) out of the two and uses that signal on the basis of previous calculation (Col 14 line 65 to Col 15 line 13) to determine the etch end point and other etch conditions like etch rate.

4. Claims 8 and 22 are rejected under 35 U.S.C. 102(e) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Matsuzawa et al (JP 2001093885).

Matsuzawa et al disclose a plasma etching apparatus capable of determining end point (Abstract) comprising a broad spectrum light source (Fig 1-20 and paragraph 40 from the English machine language translation), a spectrometer (23), a lens system (22), light source optical fiber bundle and a detector optical fiber bundle being made in a single bundle (21 and paragraph 5) and detector with discrete detection regions for detecting reflected light from an illuminated portion of a substrate (Abstract) to determine the etch end point and other etch conditions like etch rate.

Claim Rejections - 35 USC § 103

5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

6. Claims 19, 21 and 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Coronel et al (US 5658418) in view of Liu et al (20030201162).

As discussed above, Coronel discloses spectrometer to detect reflected light from the portion of the substrate illuminated but do not disclose it to be 2D CCD detector.

Liu et al disclose a plasma processing apparatus which could be used for etching (Paragraph 03) or deposition and capable of determining end point (Paragraph 0011) comprising a detector (sensor) for detecting reflected light from plasma emission by optical emission spectroscopy emanating from different discrete regions of the plasma in a direction parallel to the substrate and determining power spectrum (specific optical signal across a frequency band) for each of the different regions (Paragraph 0017) and comparing each of the power spectra to a predetermined value (model optical signal) where end point is determined from one of the detector (sensor) (Paragraph 0077). Further the optical signals are connected to each sensor from discrete region by fiber optics (Paragraph 0020) and received by a CCD array (Paragraph 49).

Therefore using CCD array as an alternative to photo diode for detection would be obvious to one of ordinary skill in the art at the time of invention.

Response to Arguments

Applicant's arguments filed 11/15/2006 have been fully considered but they are not persuasive.

Applicant argues that Coronel does not mention or suggest that optical fibers from optical cable 30 are interleaved with those of cable 32 and points to (Fig 3). However on further consideration it is disclosed that in fact the two are assembled in a single bundle of fibers.

Application/Control Number: 10/625,243

Art Unit: 1763

Conclusion

Page 5

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Ram N. Kackar whose telephone number is 571 272 1436. The

examiner can normally be reached on M-F 8:00 A.M to 5:P.M.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Parviz Hassanzadeh can be reached on 571 272 1435. The fax phone number for the

organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Primary Examiner AU 1763